In the specification:

Please amend the paragraph at page 1, lines 12-13 after the title to read as follows:

-- This application is a continuation of and claims the benefit of U.S. Patent Application

No. 10/223,719, filed August 20, 2002, which is a continuation of U.S. Patent Application No. 09/880,058, filed June 14, 2001, which is a divisional application of U.S.

Patent No. 6,271,957, issued August 7, 2001, which claims the benefit of U.S.

Provisional Application Ser. No. 60/087,333, filed May 29, 1998. U.S. Patent Application No. 10/223,719, U.S. Patent Application No. 09/880,053, U.S. Patent No. 6,271,957 and U.S. Provisional Application Ser. No. 60/087,333 are hereby incorporated by reference in

their entirety. --

Please amend the paragraph at page 12, lines 10-20 to read as follows:

-- As indicated above, substrates coated with photoresist are employed in preferred embodiments of the invention, e.g., using the DMT process with photoresist. The use of photoresist with photolithographic methods for fabricating polymer arrays is discussed in McGall et al., *Chemtech*, pp. 22-32 (February 1997); McGall et al., *Proc. Natl. Acad. Sci.*, *U.S.A.*, Vol. 93, pp. 13555-13560 (Nov. 1996) and various patents cited above, all of which are incorporated by reference in their entireties. Alternatively, polymer array synthesis processing can be performed using photoacid generators without using a conventional photoresist, e.g., using the PAG process, or using direct photodeprotection without using any photoresist, e.g., using the DPD process. The use of photoacid

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generators is taught in U.S. Application No. 08/969,227, filed November 13, 1997, now

<u>U.S. Patent 6,083,697, issued July 4, 2000</u>. However, the present invention is particularly useful when using the DMT and PAG processes for polymer array synthesis. --

Please amend the paragraph at page 17, lines 7-10 to read as follows:

-- All publications, patents and patent applications cited herein are hereby incorporated by reference in their entirety for all purposes. Application Serial No. 08/426,202 (filed April 21, 1995), now U.S. Patent No. 6,136,269, issued October 24, 2000, relates to the present invention and is hereby incorporated by reference for all purposes. --

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